

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of the claims in the application:

Listing of Claims:

1. (Previously Presented) A chemical vapor deposition system comprising: a first gas source fluidly coupled to a chemical vapor deposition chamber through a first gas distribution channel disposed within a lid of the chemical vapor deposition chamber, the lid further supporting a shower head disposed within the chemical vapor deposition chamber and separate from the first gas distribution channel, said lid having an interior rim including a plurality of cleaning gas injection ports, each of which is fluidly connected to the first gas distribution channel, and various ones of which are oriented at different angles with respect to an interior of a wall of the chemical vapor deposition chamber, said wall being attached to said lid.

2 - 4. (Cancelled)

5. (Previously Presented) The chemical vapor deposition system of claim 1, wherein the plurality of cleaning gas injection ports include a first subset of the plurality of cleaning gas injection ports disposed at a first angle relative to the interior of the wall of the chemical vapor deposition chamber, and a second subset of the plurality of cleaning gas injection ports disposed at a second angle relative to the interior of the wall.

6. (Cancelled)

7. (Previously Presented) The chemical vapor deposition system of claim 1, further including internal plumbing coupling the first gas distribution channel to the first gas source within the wall of the chemical vapor deposition chamber.

8. (Previously Presented) The chemical vapor deposition system of claim 1, further including a plurality of channel openings coupling the internal plumbing to the cleaning gas distribution channel.

9. (Previously Presented) The chemical vapor deposition system of claim 1, further including a chamber collar separating the lid of the chemical vapor deposition chamber from wall and including internal plumbing coupling the cleaning gas distribution channel to the first gas source.

10 - 21. (Cancelled)